

## ABSTRACT

## METHOD FOR MAGNETRON SPUTTERING

5       The invention relates to a method for enhancing erosion uniformity on the sputtering surface of a magnetron cathodic sputtering target. The invention is characterised in that it consists in adding to said target intended to be coupled to a magnetron maintained fixed as compared to this target, at least one ferromagnetic piece for complete or partial insertion into said target or by juxtaposition thereto, so  
10      as to bring about, at the entire sputtering surface, a curvature reduction of the magnetic induction lines generated by the magnetron.

